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10	0	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and cur\$3 and ((cutt\$6 or fold\$5) near5 (device or chamber or means))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
11	0	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and cur\$3 and ((cutt\$6 or fold\$5 or tack\$5) near5 (device or chamber or means))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

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12	0	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4 same cur\$4) and (cutter or cutt\$4) and (tack\$6) and (fold\$6) and ((resist or photoimageable or photoresist) same (liquid or ink) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB